

AMENDMENTS TO THE SPECIFICATION

Please replace the 2nd Paragraph on Page 9 with the following paragraph rewritten in amendment format:

The resin layer 20 may be patterned. Patterning refers to the removal of a region of the resin layer 20 ~~to form a penetrating space therein~~. For patterning, lithography (for example, photolithography) may be applied. In this case, a mask 30 is used.